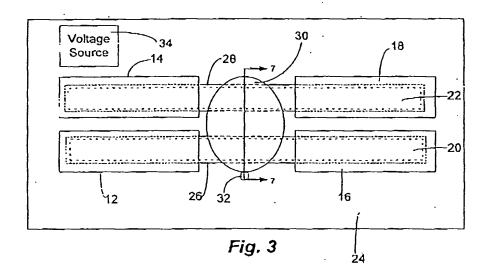
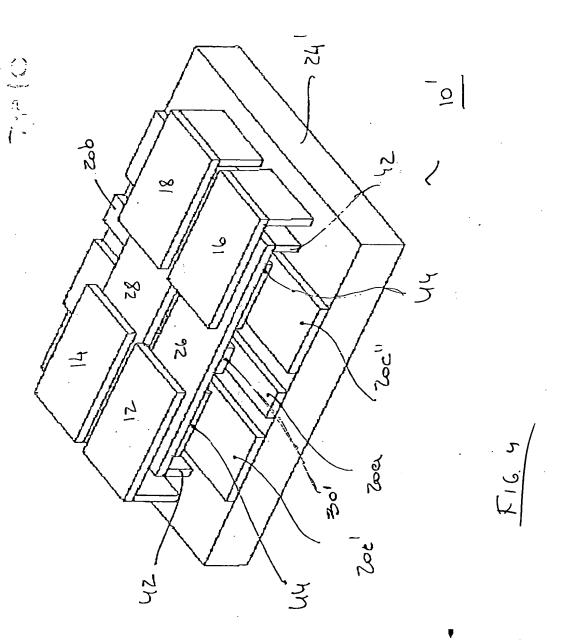
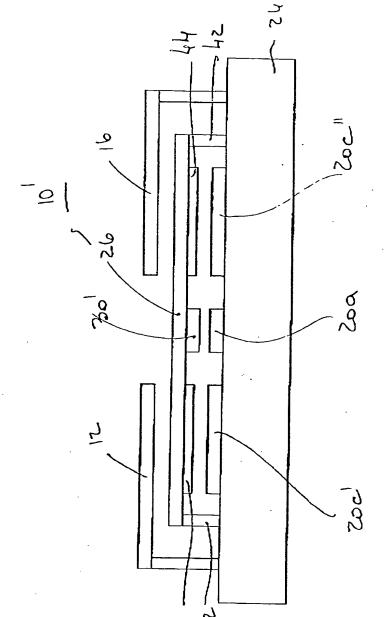


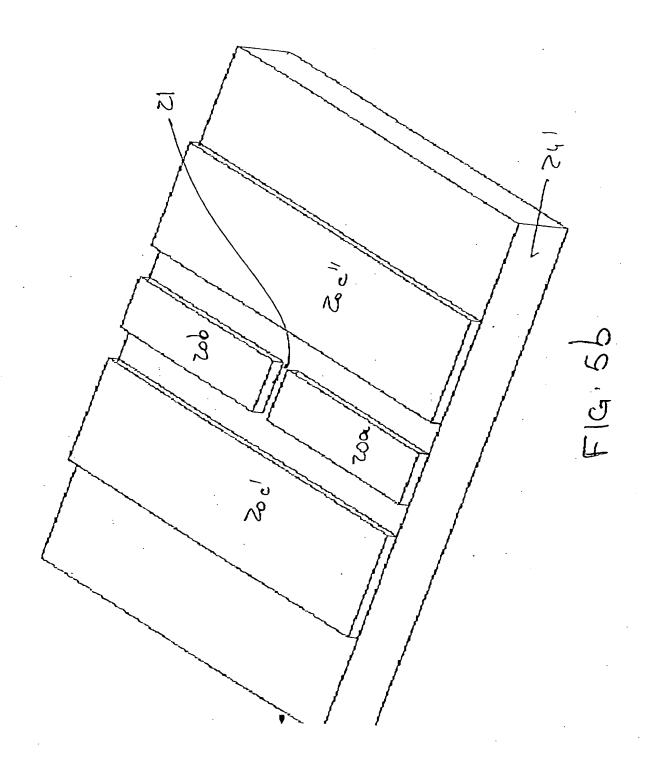
Fig. 2



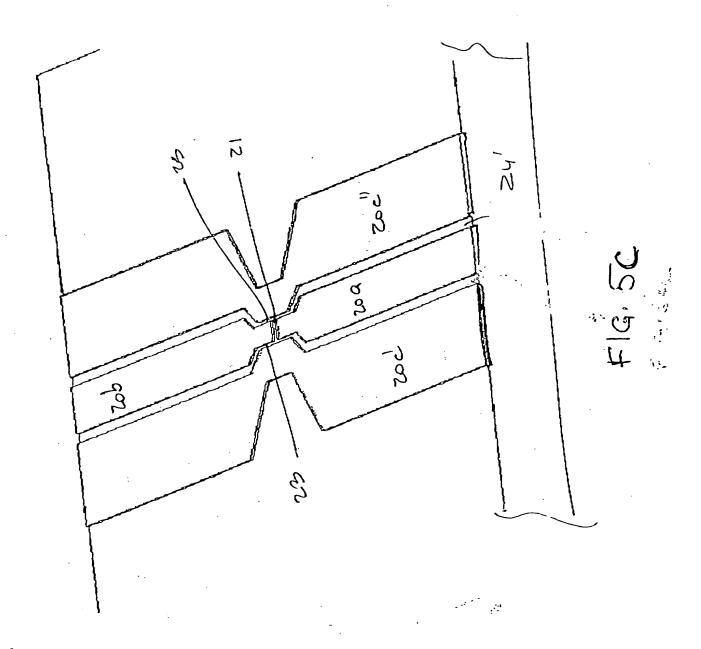




F19 . 29







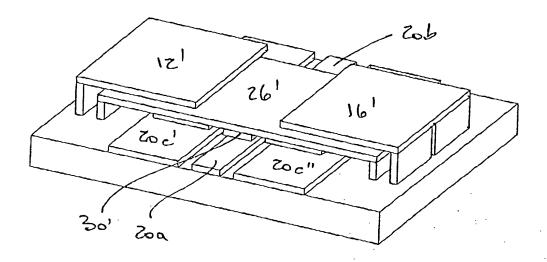
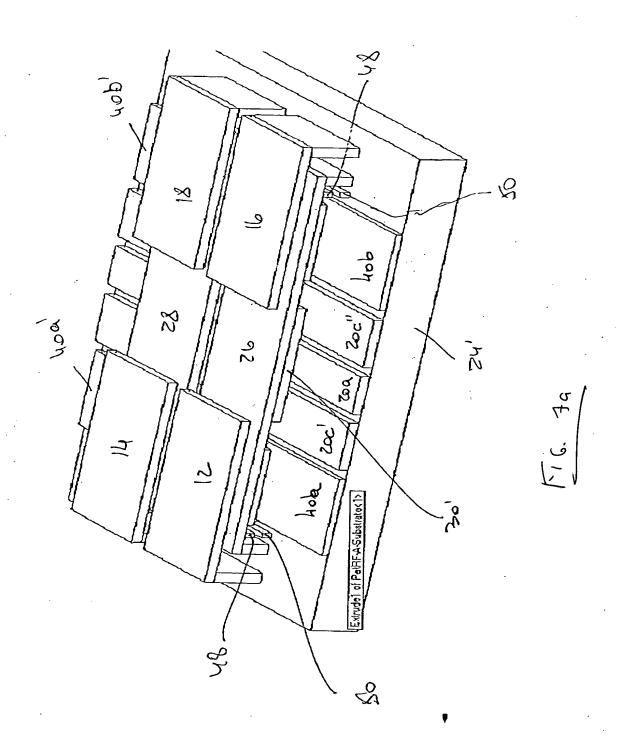
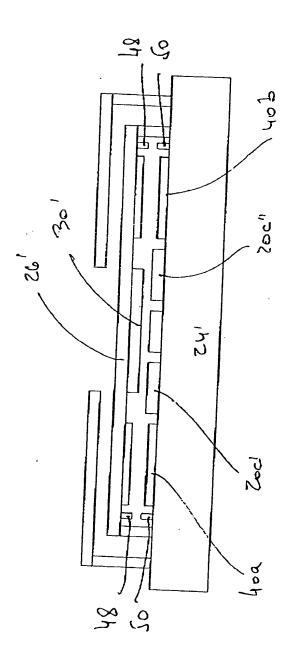
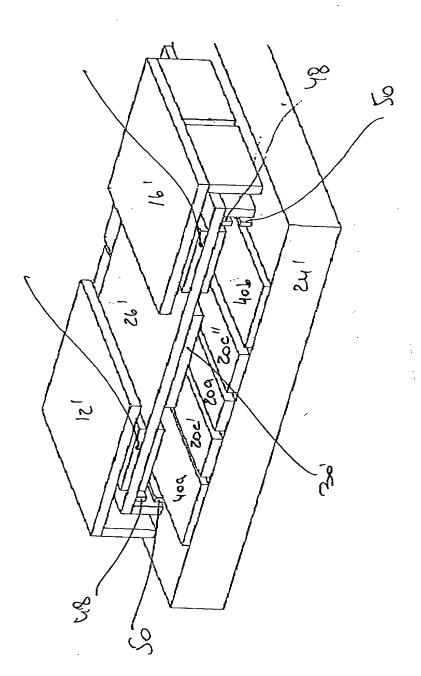


FIG 6

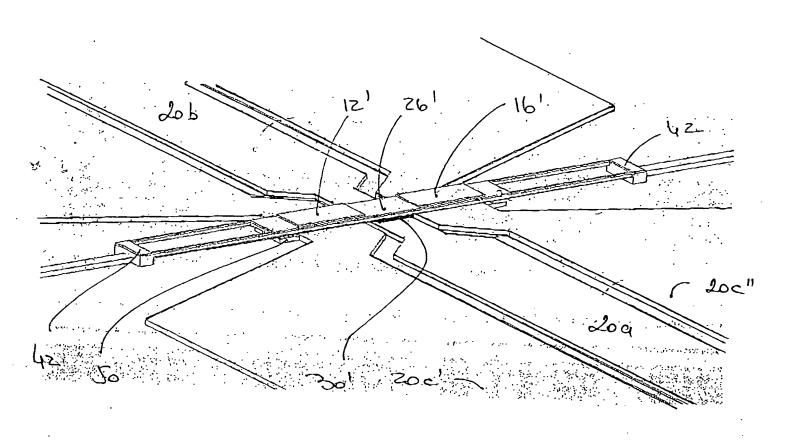




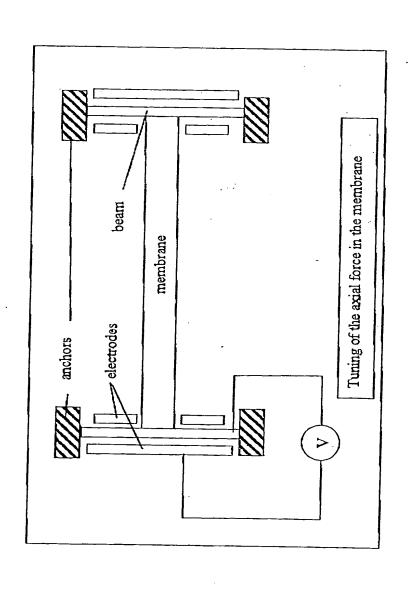
F1G.75

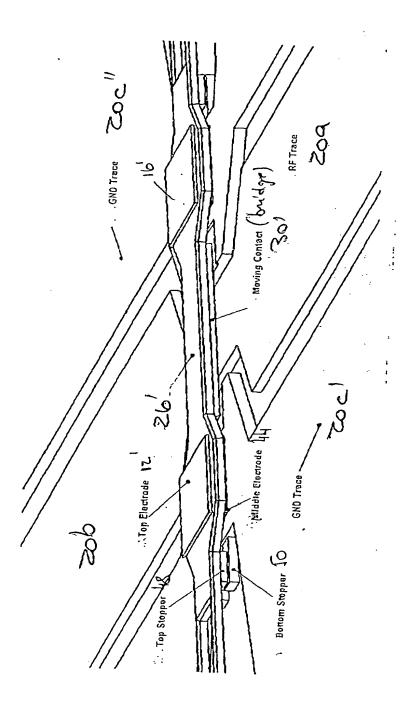


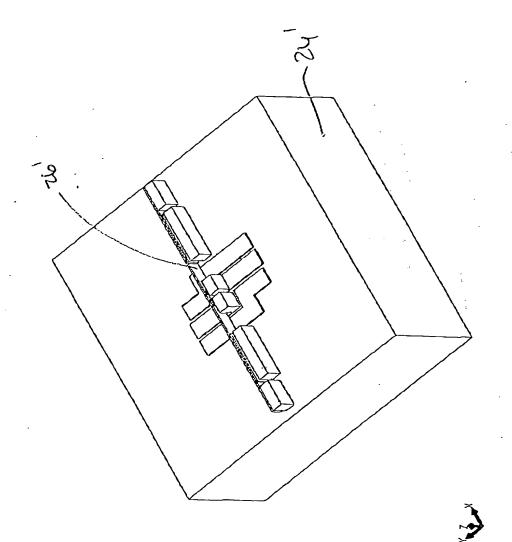
7 10 - R



F19,3







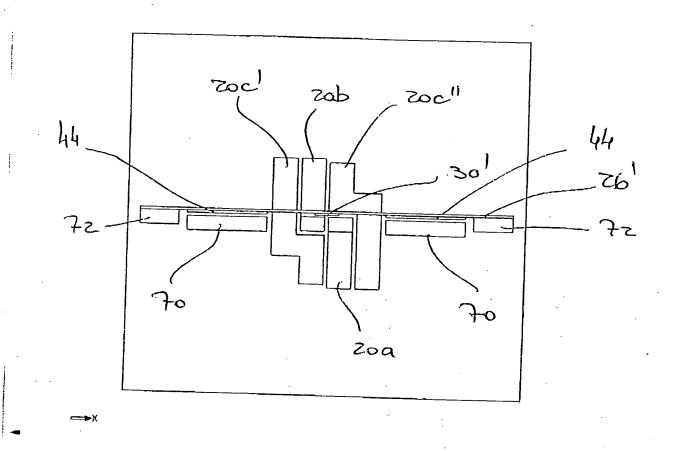
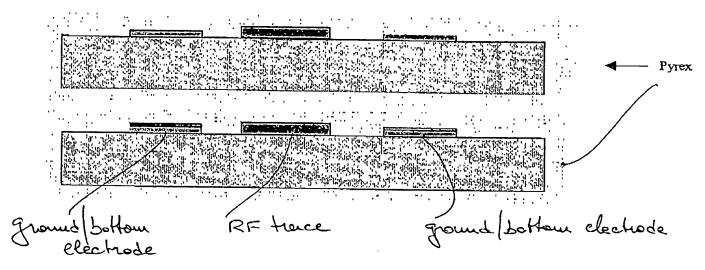
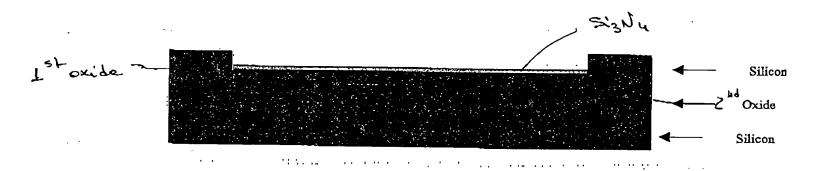


FIG. 126

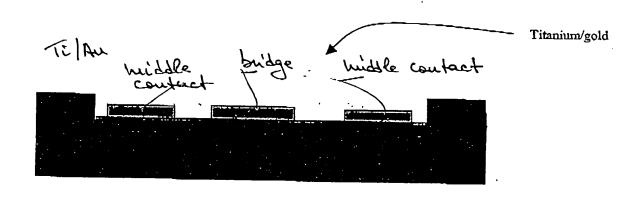
'n



a: Wafer 1 Contact line

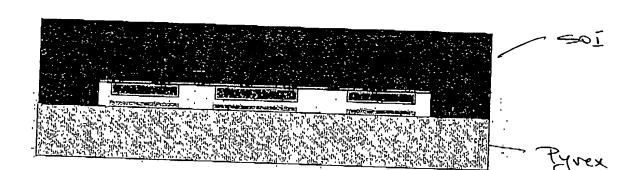


b: Wafer 2 First RIE and Nitride deposition



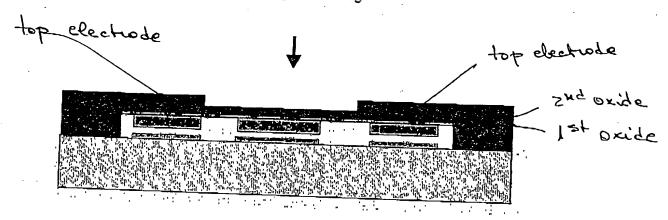
c: Wafer 2 Contact Bridge and Electrodes

F19.13

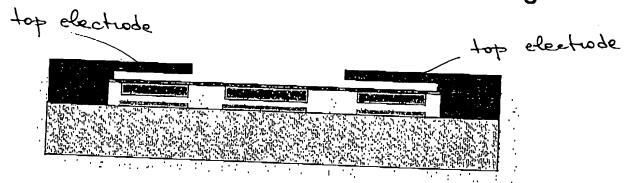


d: Wafer Bonding

Polishing and etching



e: Polishing and top electrodes etching



f: Structure R lease

FIG. 13 Continued